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(12) **United States Design Patent**
Chen

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(54) **MASK**

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(**) **Term:** **14 Years**

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(51) **LOC (9) Cl.** **29-02**

(52) **U.S. Cl.** **D29/110**

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D29/122; D24/110.1-110.4, 191; 267/142-146,
267/113, 64.13; 2/410-414, 416, 422-425,
2/9, 10, 206, 427, 429, 5, 6.3, 6.5, 6.7; 128/857-858
See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a mask showing my design;

FIG. 2 is a front elevational view thereof;

FIG. 3 is a rear elevational view thereof;

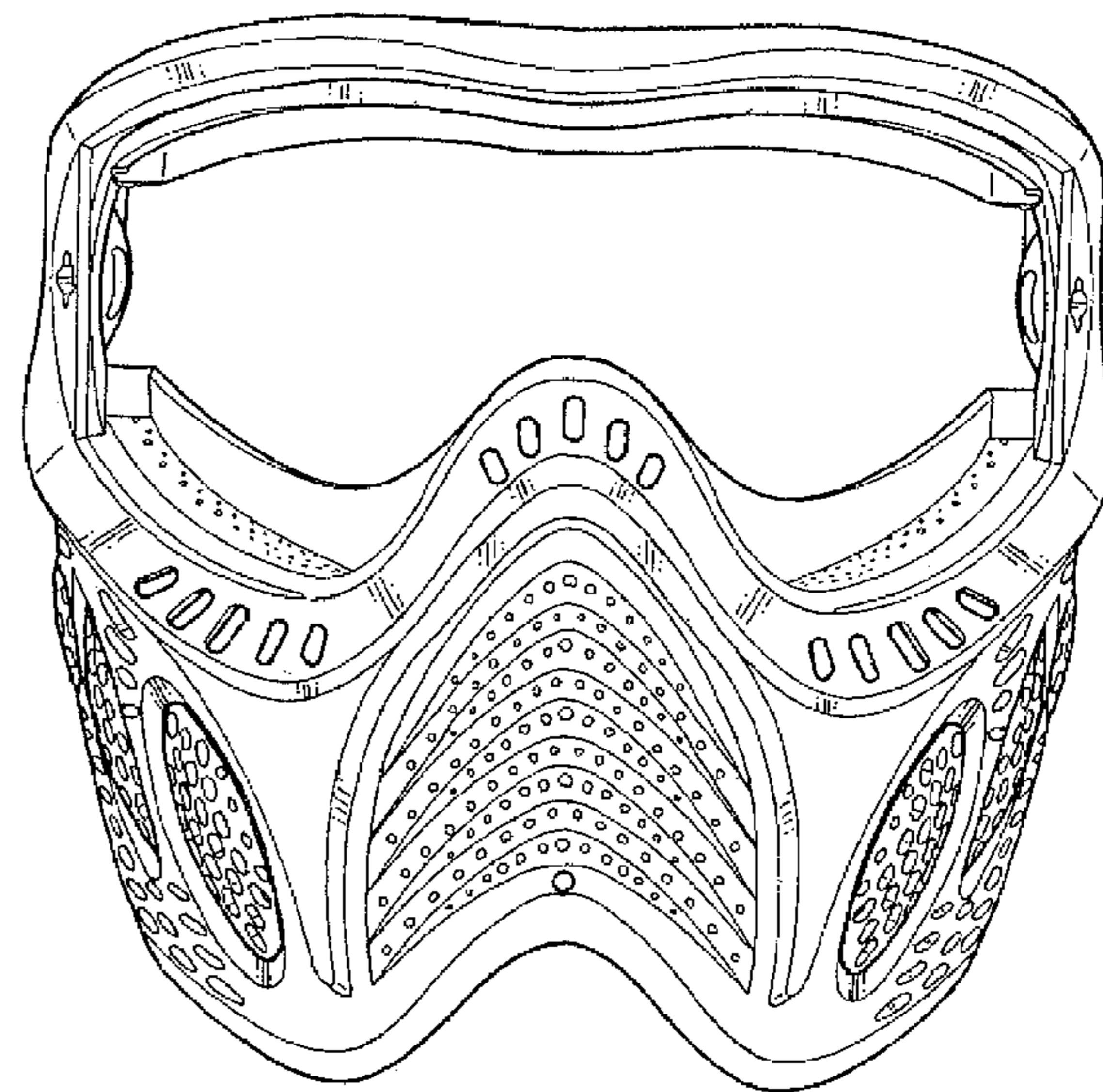
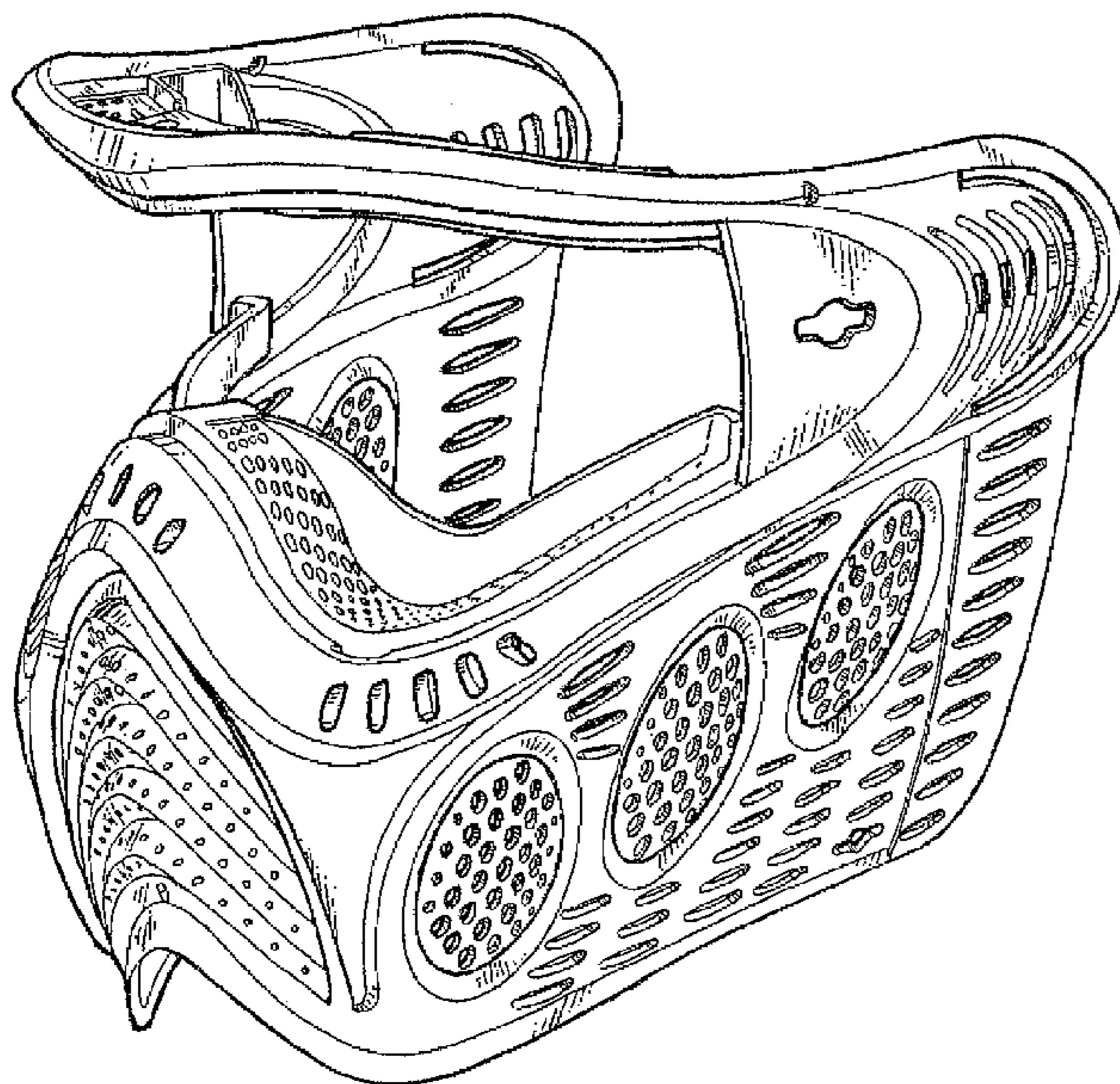
FIG. 4 is a left side elevational view thereof;

FIG. 5 is a right side elevational view thereof;

FIG. 6 is a top plan view thereof; and,

FIG. 7 is a bottom plan view thereof.

1 Claim, 7 Drawing Sheets



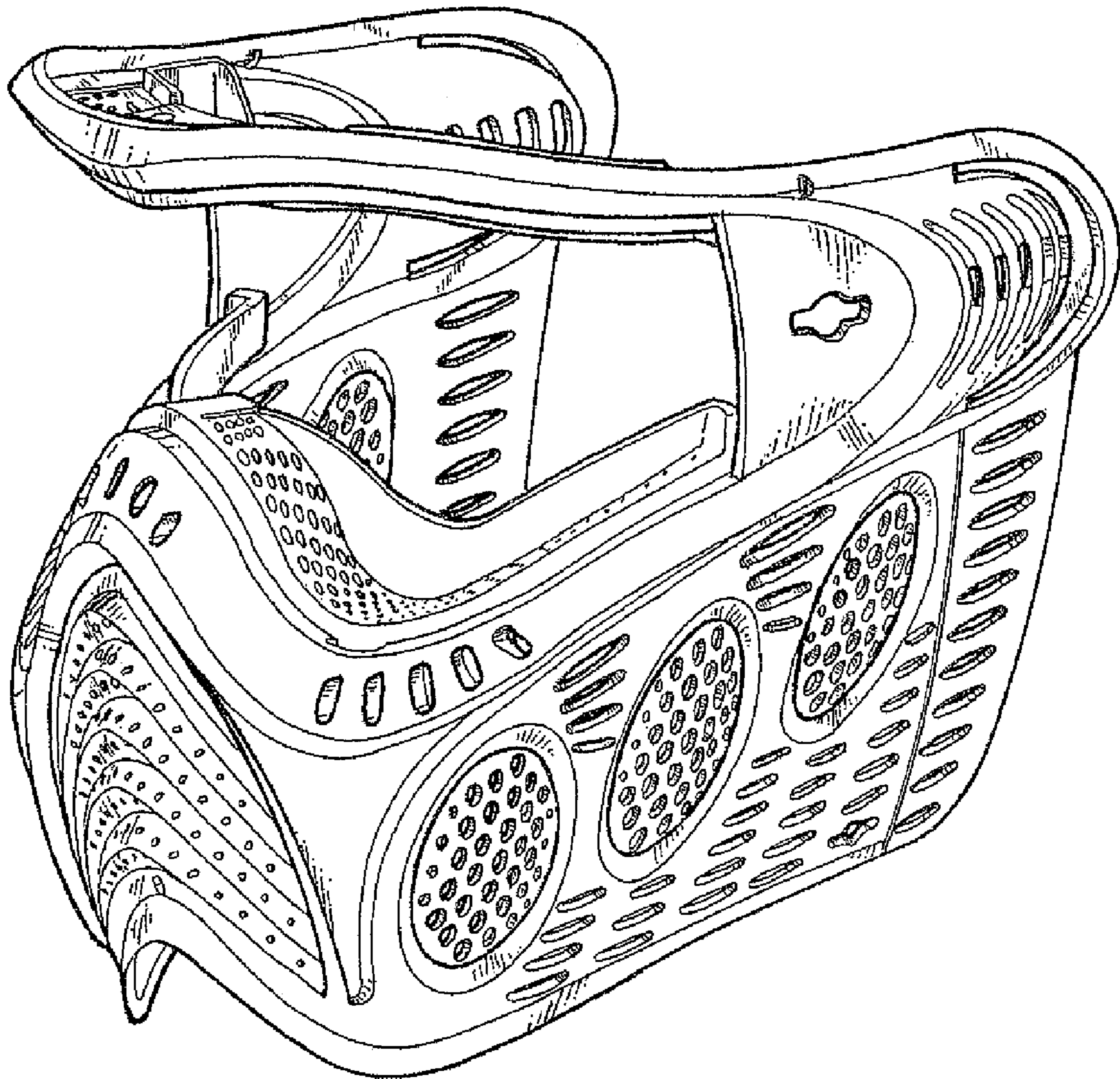


FIG.1



FIG.2



FIG.3

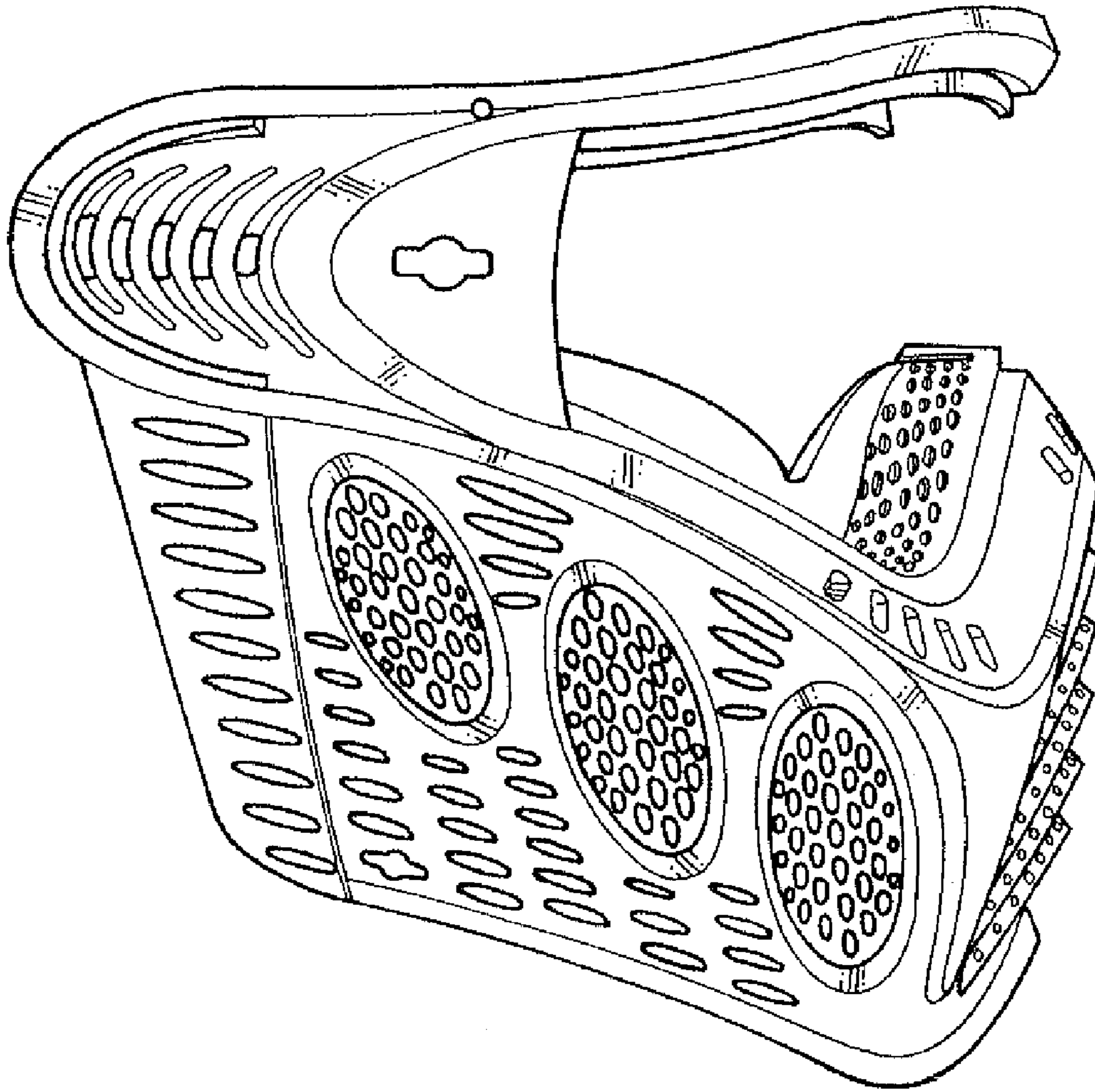


FIG.4

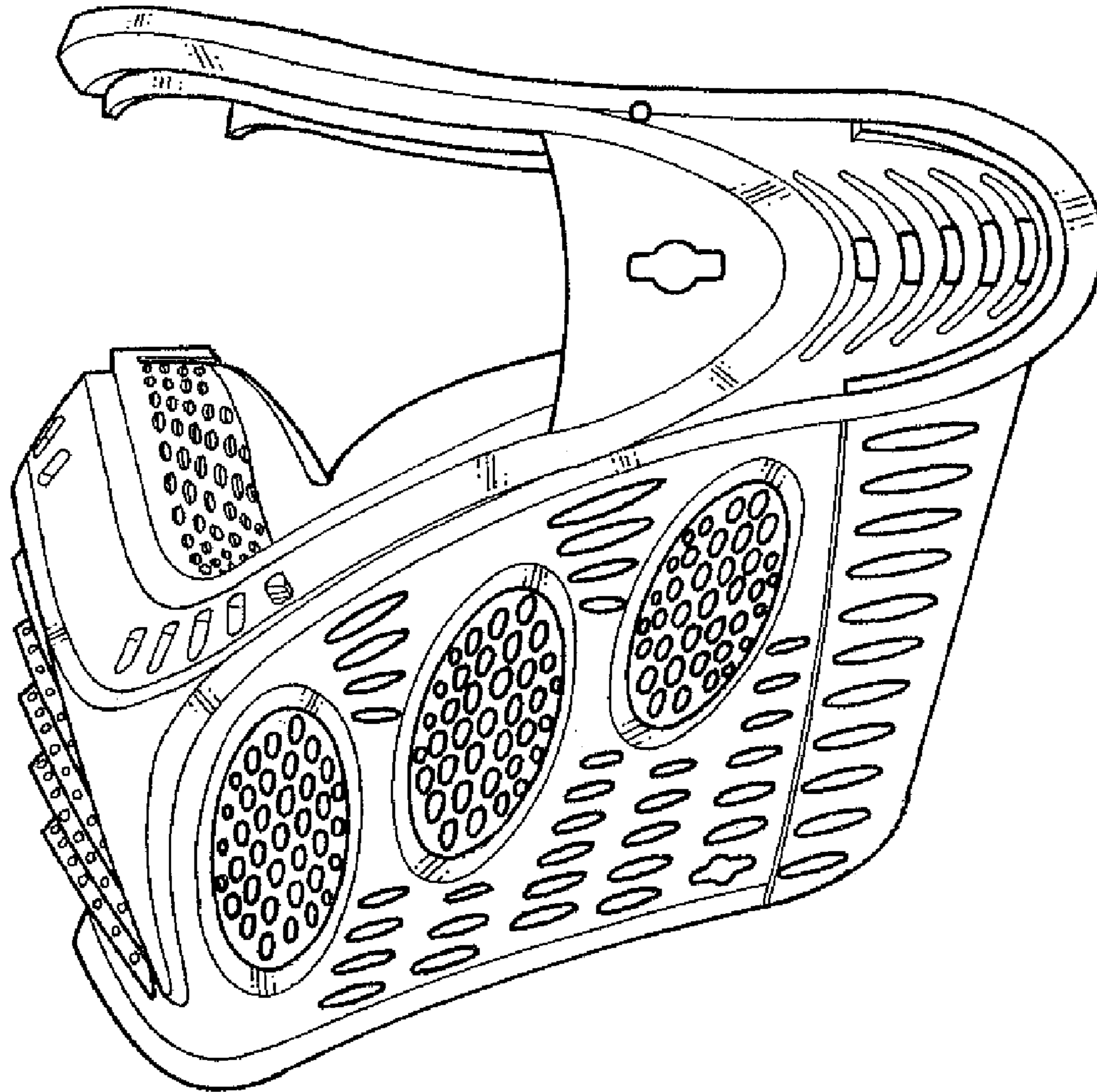


FIG.5

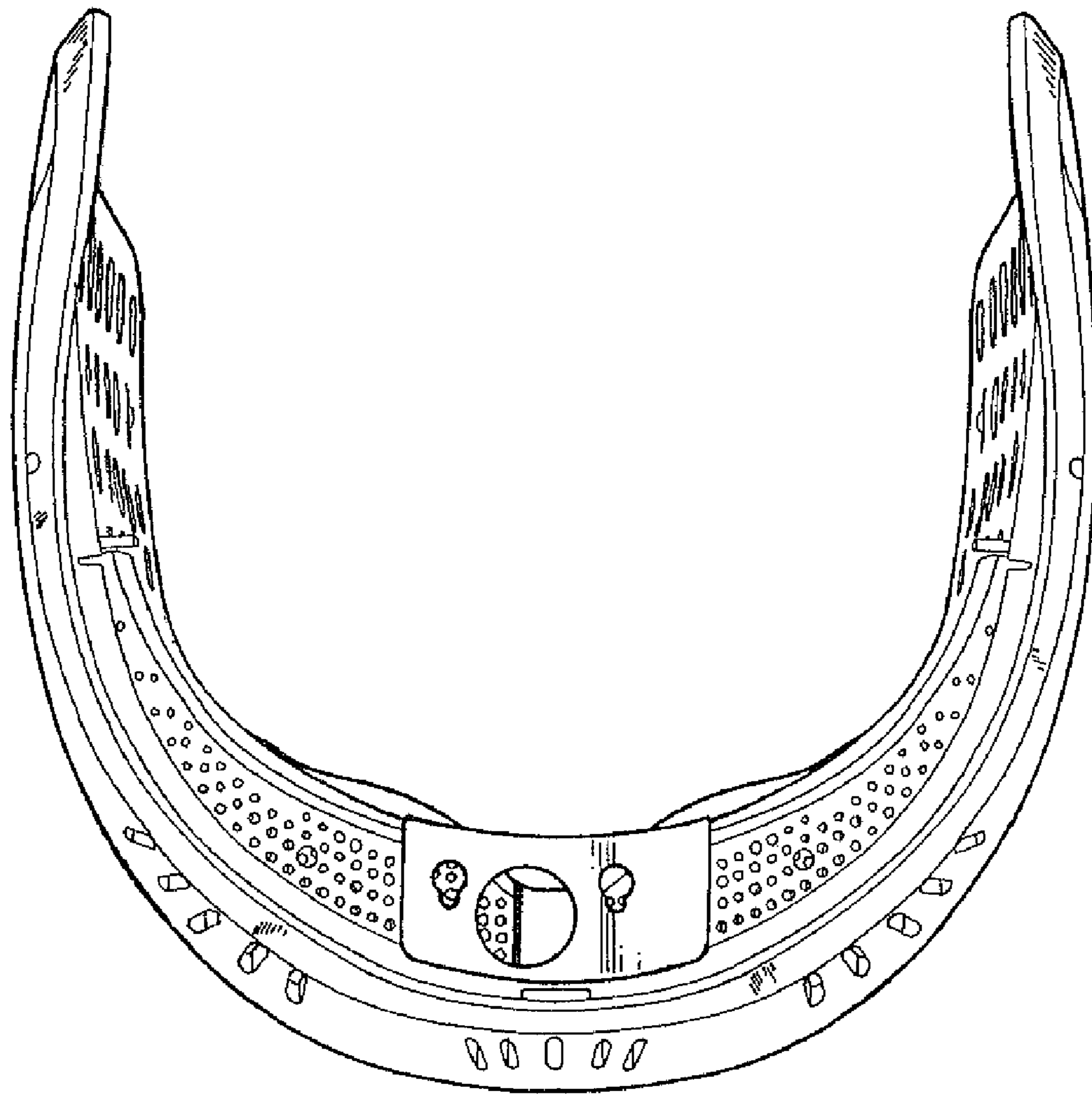


FIG.6

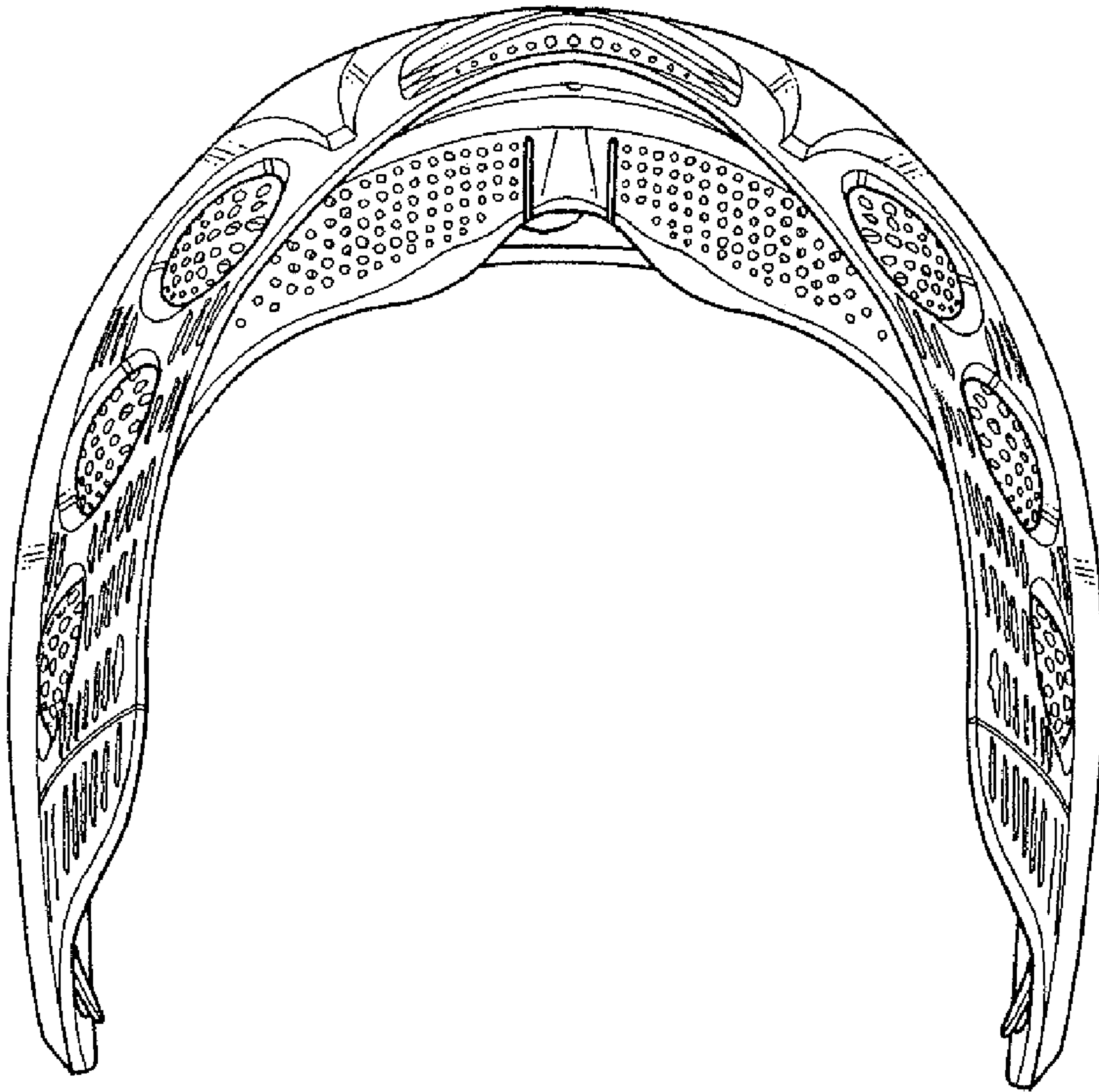


FIG.7